

# Application News

## Inductively Coupled Plasma Mass Spectrometer ICPMS-2050

## Analysis of Metal Elements in Culture Medium Using ICPMS-2050

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## **User Benefits**

- Analysis of both trace and high-concentration elements is possible in culture media.
- Culture media can be analyzed with simple dilution-only pretreatment using the ICPMS-2050.
- The elements in the culture medium can be analyzed reliably and accurately over a long period.

## Introduction

A culture medium usually contains elements spanning a wide range of concentrations, from trace (Co, Cu, Se, etc.) to several thousand ppm (Na). Elements in the medium are important in cell cultures because they are taken up by the cells and contribute to enzyme activity and redox reactions. On the other hand, it has been pointed out that unexpected contamination from raw materials and equipment in the culture media manufacturing process may cause differences in element concentrations among batches. Therefore, it is important to know the element concentration profiles in the culture medium to achieve a homogeneous cell culture.

ICP-MS is suitable for this purpose because it can analyze multiple elements with high sensitivity and has a wide dynamic range. In this Application News, an ICPMS-2050 was used to analyze both trace and high-concentration elements in a culture medium by dilution-only pretreatment. Furthermore, the spike recovery and long-term stability in the culture medium were evaluated using the ICPMS-2050 to confirm that there was no effect on the analytical value due to dilution-only pretreatment.

## Analysis Elements

Trace elements: Ag, Al, Ba, Bi, Cd, Co, Cr, Cu, Fe, Ge, Li, Mn, Mo, Ni, Se, Sn, Ti, V, Zn

High-concentration elements: Ca, K, Mg, Na, P

## Samples and Pretreatment

### Analytical Samples

DMEM (high glucose) was used as an analytical sample. In addition, to evaluate the influence of proteins produced during the cultivation process on the analysis, a high-matrix medium was prepared by adding purified protein at a concentration of 10 g/L to DMEM (Hereafter referred to as high matrix medium).

Pretreatment

Unspiked samples: Unspiked samples were prepared by diluting culture media 20 times with mixed acid (1v/v% nitric acid and 0.5v/v% hydrochloric acid).

Spiked samples: Spiked samples were prepared by adding single-element standard solutions and diluting the culture media 20 times with mixed acid (1v/v% nitric acid and 0.5v/v% hydrochloric acid).

## Standard Samples

#### Calibration Standards

Calibration curve standards were prepared by mixing commercially available single-element standard solutions and diluting them with mixed acid (1v/v%) nitric acid and 0.5v/v% hydrochloric acid). The concentrations in each calibration curve standard are shown in Table 1.

Internal Standard Solution

The internal standard solution was prepared by mixing commercially available single-element standard solutions (Be, Ga, Sc, Rh, Tl) and diluted with mixed acid (1v/v% nitric acid and 0.5v/v% hydrochloric acid). The concentrations of Be, Ga, and Sc in the internal standard solution were 1 mg/L, and the concentrations of Rh and Tl were 0.2 mg/L.

• Continuing Calibration Verification (CCV) Sample CCV was prepared at the same concentration as STD3.

Table 1 Calibration Curve Standards

Elemente.	1114	Concentration						
Elements	Unit	STD0	STD1	STD2	STD3	STD4	STD5	
Ag, Al, Ba, Bi, Cd, Co, Cr, Cu, Fe, Ge, Li, Mn, Mo, Ni, Se, Sn, V, Zn	μg/L	0	0.5	1	5	10		
Ti	μg/L	0	5	10	50	100		
Ca, Mg, P	mg/L	0		1	5	10		
к	mg/L	0		2.5	12.5	25		
Na	mg/L	0			30	60	300	

## Equipment Configuration and Analytical Conditions

The configuration of the ICP-MS system is shown in Table 2. To reduce running costs, the analysis was performed using a minitorch, which consumes less argon gas than a normal plasma torch. To save labor in sample preparation, the internal standards were added online using an online internal standard kit.

Table 3 shows the analytical conditions.

Table 2 ICP-MS System Configuration						
System:	ICPMS-2050					
Nebulizer:	Nebulizer DC04					
Chamber:	Cyclone Chamber					
Torch:	Mini-Torch					
Skimmer Cone:	Nickel					
Sampling Cone:	Nickel					
Autosampler:	AS-20					
Internal Standard Elements:	Online Internal Standard Kit (sample: internal standard = about 9: 1)					

Table 3 Analytical Conditions					
RF Power:	1.20 kW				
Sampling Depth:	7.0 mm				
Plasma Gas Flowrate:	9.0 L/min				
Auxiliary Gas Flowrate:	1.10 L/min				
Carrier Gas Flowrate:	0.60 L/min				
Dilution Gas Flowrate:	0.25 L/min				
Pump Speed:	15 r.p.m.				
Collision / Reaction Gas:	He / H <sub>2</sub>				

## Sample Analysis and Spike Recovery

Analytical samples were quantitatively analyzed using the calibration curves shown in Table 1.

Table 4 shows the quantification results for the solution and the culture medium. The results for the culture medium were calculated by dilution factor. It was found that the simultaneous analysis of multiple elements in the culture medium that are present in a wide range of concentrations, from sub-ppb to several thousand ppm, is possible.

Furthermore, DMEM and high matrix media spike recovery tests were conducted to demonstrate that dilution-only pretreatment had no effect on the analytical values. The spike recoveries were calculated, and the results are shown in Table 5. Spike recoveries of 94 to 107% were obtained for all the measured elements, showing that the culture medium can be accurately analyzed with dilution-only pretreatment using the ICPMS-2050.

Elements						DM	EM	High Matrix Medium	
		Collision / Reaction Gas	Internal Standard Element	Instrument Detection Limit (IDL)*	DL in Sample**	Mean Measured Value in Solution	Mean Measured Value in Sample	Mean Measured Value in Solution	Mean Measured Value in Sample
	<sup>107</sup> Ag	He	<sup>103</sup> Rh	0.005	0.1	N.D.***	N.D.	N.D.	N.D.
	<sup>27</sup> AI	No Gas	<sup>45</sup> Sc	0.05	1	0.06	1	4.57	91.4
	<sup>138</sup> Ba	He	<sup>103</sup> Rh	0.005	0.1	0.016	0.32	0.517	10.3
	<sup>209</sup> Bi	He	<sup>205</sup> Tl	0.002	0.04	N.D.	N.D.	0.003	0.06
Trace Elements (μg/L)	<sup>111</sup> Cd	He	<sup>103</sup> Rh	0.01	0.2	N.D.	N.D.	N.D.	N.D.
	<sup>59</sup> Co	He	<sup>71</sup> Ga	0.01	0.2	N.D.	N.D.	0.06	1
	<sup>52</sup> Cr	He	<sup>71</sup> Ga	0.02	0.4	0.02	0.4	0.17	3.4
	<sup>63</sup> Cu	He	<sup>71</sup> Ga	0.006	0.1	0.007	0.1	0.599	12.0
	<sup>56</sup> Fe	H <sub>2</sub>	<sup>71</sup> Ga	0.01	0.2	0.73	15	3.87	77.4
	<sup>72</sup> Ge	He	<sup>71</sup> Ga	0.03	0.6	N.D.	N.D.	N.D.	N.D.
	<sup>7</sup> Li	No Gas	9Be	0.003	0.06	0.007	0.1	0.020	0.40
	⁵⁵Mn	He	<sup>71</sup> Ga	0.02	0.4	N.D.	N.D.	0.05	1.0
	<sup>98</sup> Mo	He	<sup>103</sup> Rh	0.007	0.1	N.D.	N.D.	0.022	0.44
	<sup>60</sup> Ni	He	<sup>71</sup> Ga	0.02	0.4	0.02	0.4	0.40	8.0
	<sup>78</sup> Se	H <sub>2</sub>	<sup>71</sup> Ga	0.01	0.2	N.D.	N.D.	0.07	1
	<sup>118</sup> Sn	He	<sup>103</sup> Rh	0.02	0.4	N.D.	N.D.	N.D.	N.D.
	<sup>47</sup> Ti	He	<sup>45</sup> Sc	0.5	10	N.D.	N.D.	N.D.	N.D.
	<sup>51</sup> V	He	<sup>45</sup> Sc	0.03	0.6	N.D.	N.D.	N.D.	N.D.
	<sup>66</sup> Zn	He	<sup>71</sup> Ga	0.02	0.4	N.D.	N.D.	0.11	2.2
	<sup>44</sup> Ca	He	<sup>45</sup> Sc	0.05	1	3.52	70.4	3.48	69.6
High- Concentration Elements (mg/L)	<sup>39</sup> K	He	<sup>45</sup> Sc	0.008	0.2	10.7	214	10.6	212
	<sup>24</sup> Mg	He	<sup>45</sup> Sc	0.0008	0.02	0.971	19.4	0.965	19.3
	<sup>23</sup> Na	He	<sup>45</sup> Sc	0.04	0.8	178	3560	177	3540
	<sup>31</sup> P	He	<sup>45</sup> Sc	0.02	0.4	1.44	28.8	1.40	28.0

Table 4 Quantification Results in the Solution and in the Culture Medium

\*IDL: 3 imes  $\sigma$  (standard deviation of calibration solution's blank) imes slope of the calibration curve

\*\*DL in Sample: IDL imes dilution times (20 times)

\*\*\*N.D.: below the detection limit

Elements		Instrument		DMEM	Spiked DMEM		High Spiked High Matrix Matrix Medium		gh Matrix ium
		Detection Limit (IDL)*	Spike Concentration	Mean Measured Value in Solution	Mean Measured Value in Solution	Recovery (%)	Mean Measured Value in Solution	Mean Measured Value in Solution	Recovery (%)
	<sup>107</sup> Ag	0.005	5	N.D.**	4.93	99	N.D.	4.94	99
	<sup>27</sup> AI	0.05	5	0.06	5.06	100	4.57	9.93	107
	<sup>138</sup> Ba	0.005	5	0.016	5.10	102	0.517	5.72	104
	<sup>209</sup> Bi	0.002	5	N.D.	4.90	98	0.003	4.91	98
	<sup>111</sup> Cd	0.01	5	N.D.	4.91	98	N.D.	4.92	98
	<sup>59</sup> Co	0.01	5	N.D.	4.96	99	0.06	4.98	98
Trace Elements (μg/L)	<sup>52</sup> Cr	0.02	5	0.02	5.09	101	0.17	5.33	103
	<sup>63</sup> Cu	0.006	5	0.007	4.85	97	0.599	5.39	96
	<sup>56</sup> Fe	0.01	5	0.73	5.65	98	3.87	8.98	102
	<sup>72</sup> Ge	0.03	5	N.D.	4.98	100	N.D.	4.94	99
	<sup>7</sup> Li	0.003	5	0.007	4.98	98	0.020	4.74	94
	<sup>55</sup> Mn	0.02	5	N.D.	5.02	100	0.05	5.16	102
	<sup>98</sup> Mo	0.007	5	N.D.	5.12	102	0.022	5.11	102
	<sup>60</sup> Ni	0.02	5	0.02	4.92	98	0.40	5.28	98
	<sup>78</sup> Se	0.01	5	N.D.	4.95	99	0.07	5.36	106
	<sup>118</sup> Sn	0.02	5	N.D.	5.03	101	N.D.	5.07	101
	<sup>47</sup> Ti	0.5	50	N.D.	50.8	101	N.D.	50.6	101
	<sup>51</sup> V	0.03	5	N.D.	4.98	100	N.D.	4.90	98
	<sup>66</sup> Zn	0.02	5	N.D.	4.83	97	0.11	4.99	98
High- Concentration Elements (mg/L)	<sup>44</sup> Ca	0.05	5	3.52	8.51	100	3.48	8.52	101
	<sup>39</sup> K	0.008	12.5	10.7	23.0	98	10.6	23.4	102
	<sup>24</sup> Mg	0.0008	5	0.971	5.84	97	0.965	5.91	99
	<sup>23</sup> Na	0.04	100	178	277	99	177	283	106
	<sup>31</sup> P	0.02	5	1.44	6.56	102	1.40	6.67	105

## Table 5 Result of Spike Recovery

\*IDL: 3  $\times$   $\sigma$  (standard deviation of calibration solution's blank)  $\times$  slope of the calibration curve \*\*N.D.: below the detection limit

## ■ Long-Term Stability

Both DMEM and high matrix media were analyzed for approximately 8 hours to evaluate the long-term stability of the ICPMS-2050. CCV was measured every 10 samples (100 samples in total) to confirm the validity of the calibration curves. Recoveries of CCV during the analysis are shown in Fig. 1.

The CCV recoveries of all the measured elements during the analysis were within 90 to 110 % (red dotted line), which confirmed the validity of the calibration curve during the long-term analysis.

In addition, the internal standard recoveries during analysis are shown in Fig. 2. The intensity of each internal standard element in STD0 was defined as 100 %. All measured internal standard recoveries were within 70 to 130 % (red dotted line). The CCV and internal standard recoveries showed good long-term stability of ICPMS-2050 analysis.



Fig. 1 CCV Recoveries over 8 Hours Analysis



Fig. 2 Internal Standard Recoveries over 8 Hours Analysis

## Summary

In this Application News, the ICPMS-2050 was used to analyze trace and high-concentration elements in a culture medium using dilution-only pretreatment. Good spike recoveries were obtained for all the measured elements, verifying that the culture medium can be accurately analyzed with dilution-only pretreatment. In addition, the results of CCV and internal standard recoveries showed good long-term stability.



## <References>

1) Ryan J. Graham et al., "Consequences of trace metal variability and supplementation on Chinese hamster ovary (CHO) cell culture performance: A review of key mechanism and considerations," Biotechnology and Bioengineering, 2019

<Related Applications>

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